



PATENT

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Applicant: PERRY et al.

Examiner: F. Evans

JUL 21 2000

Applicant's Reference: LAM1P100

Group Art Unit: 2877

Application No: 09/409,842

Issue Batch No: K08

### OFFICE OF PETITIONS

Filed: September 30, 1999

Notice of Allowability Date: June 26, 2000

Title: METHOD AND APPARATUS FOR IN-SITU MONITORING OF PLASMA ETCH  
AND DEPOSITION PROCESSES USING A PULSED BROADBAND LIGHT SOURCE

### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the  
United States Postal Service as First Class Mail in an envelope addressed  
to: Assistant Commissioner for Patents, Washington, DC 20231 on  
July 13, 2000.

Signed: Yvonne Mock

Yvonne Mock

### Separate Letter to the Official Draftsman

Assistant Commissioner for Patents  
Box: ISSUE FEE  
Washington, D.C. 20231

Dear Sir:

In response to the objections raised by the Draftsman in an action dated June 26, 2000, enclosed are the corrected formal drawings (Figures 1, 2, 3,) for the above-identified patent application. If the Draftsman has any question concerning the corrected drawings, he or she is respectfully requested to contact the undersigned.

Respectfully submitted,

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Attorney Docket No. LAM1P100